

Tecnical Data - RIE SYSTEM

Process chamber	Up to Ø 500 mm, high up to 200 mm
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Electrodes	Up to Ø 400 mm
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Substrate holder	Up to 8"
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Ultimate Pressure	Range 10 ⁻⁷ mbar
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RF power supply 13.56 MHz	Up to 2500 W
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